

FEB 26 2007

Docket No.: 020732-97.668 (7493)  
Appl. No. 10/792,038IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

<b>In re United States Patent Application of:</b>	) Docket No.:	<b>020732-97.668</b>
	)	(7493)
<b>Applicants:</b> RATH, Melissa K., et al.	) Conf. No.:	<b>4823</b>
<b>Application No.:</b> 10/792,038	) Art Unit:	<b>1752</b>
<b>Date Filed:</b> March 3, 2004	) Examiner:	<b>LE, Hoa Van</b>
<b>Title:</b> COMPOSITION AND PROCESS FOR POST-ETCH REMOVAL OF PHOTORESIST AND/OR SACRIFICIAL ANTI-REFLECTIVE MATERIAL DEPOSITED ON A SUBSTRATE	) Customer No.:	<b>24239</b>

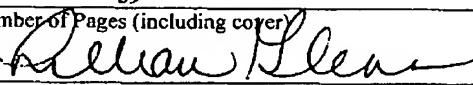
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Attn: Examiner Hoa Van Le  
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Number of Pages (including cover)

  
Lillian Glenn

February 26, 2006  
Date

RESPONSE TO NOVEMBER 24, 2006 OFFICE ACTION IN UNITED STATES PATENT  
APPLICATION NO. 10/792,038

Mail Stop Amendment  
Commissioner for Patents  
PO Box 1450  
Alexandria, VA 22313-1450

Sir:

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**Please amend the claims, as set out in the following Section I (the Claims).**

Remarks addressing the substance of the November 24, 2006 Office Action are set out in the  
**Section II (Remarks)** hereof.